

**Amendments to the Claims:**

This listing of claims will replace all prior versions, and listings, of claims in the application:

**Listing of Claims:**

Claim 1 (Previously Amended): A method for creating recordable regions and non-recordable regions in a recording layer, the method comprising the steps of:

forming a mask over the recording layer;

defining a pattern in the mask leaving an exposed portion of the recording layer, wherein the pattern defines the recordable regions and the non-recordable regions to be created in at least one layer in the recording layer;

changing the magnetic properties of portions of the recording layer by exposing the mask and the exposed portions of the recording layer to a plasma, wherein the magnetic properties of at least one layer in the exposed portions of the recording layer are changed, in order to create recordable regions or non-recordable regions in the recording layer; and

removing the mask.

Claim 2 (original): The method of claim 1, wherein the recording layer is comprised of a single, dual, or multi-layer recording layer.

Claim 3 (canceled):

Claim 4 (Previously Amended): The method of claim 3 2, wherein the step of defining a pattern in the mask comprises the step of defining a pattern in the mask using photolithography.

Claim 5 (original): The method of claim 4, wherein the step of defining a pattern in the mask using photolithography exposes portions of the recording layer.

Claim 6 (original): The method of claim 5, wherein the step of changing the magnetic properties of portions of the recording layer comprises the step of exposing the mask and the exposed portions of the recording layer to a plasma, wherein the magnetic properties of at least one layer in the exposed portions of the recording layer are changed.

Claim 7 (original): The method of claim 5, further comprising the step of etching away a portion of the recording layer in the exposed portions of the recording layer, wherein grooves are formed in at least one layer within the exposed portions of the recording layer.

Claim 8 (original): The method of claim 7, wherein the step of changing the magnetic properties of portions of the recording layer comprises the step of exposing the mask and the exposed portions of the recording layer to a plasma, wherein the magnetic properties of at least one layer in the exposed portions of the recording layer are changed.

Claim 9 (original): The method of claim 3, wherein the step of defining a pattern in the mask comprises the step of defining a pattern in the mask using imprint lithography.

Claim 10 (original): The method of claim 9, further comprising the step of removing at least a portion of the mask after performing imprint lithography, wherein portions of the recording layer are exposed.

Claim 11 (original): The method of claim 10, wherein the step of changing the magnetic properties of portions of the recording layer comprises the step of exposing the mask and the exposed portions of the recording layer to a plasma, wherein the magnetic properties of at least one layer in the exposed portions of the recording layer are changed.

Claim 12 (original): The method of claim 10, further comprising the step of etching away a portion of the recording layer in the exposed portions of the recording layer, wherein grooves are formed in at least one layer within the exposed portions of the recording layer.

Claim 13 (original): The method of claim 12, wherein the step of changing the magnetic properties of portions of the recording layer comprises the step of exposing the mask and the exposed portions of the recording layer to a plasma, wherein the magnetic properties of at least one layer in the exposed portions of the recording layer are changed.

Claim 14 (Previously Amended): A system for creating recordable regions and non-recordable regions in a recording layer, the system comprising:

means for placing a mask over the recording layer, wherein the mask includes a pattern that defines the recordable regions and the non-recordable regions to be created in the recording layer;

means for changing the magnetic properties of portions of the recording layer by exposing the mask and the exposed portions of the recording layer to a plasma, wherein the magnetic properties of at least one layer in the exposed portions of the recording layer are changed, in order to create recordable regions or non-recordable regions in the recording layer; and

means for removing the mask.

Claim 15 (original): The system of claim 14, wherein the recording layer is comprised of a single, dual, or multi-layer recording layer.

Claim 16 (original): The system of claim 15, wherein the means for placing a mask over the recording layer comprises:

means for forming a mask over the recording layer; and

means for defining a pattern in the mask, wherein the pattern defines the recordable regions and the non-recordable regions to be created in at least one layer in the recording layer.

Claim 17 (original): The system of claim 16, wherein the means for defining a pattern in the mask exposes portions of the recording layer.

Claim 18 (original): The system of claim 17, wherein the means for changing the magnetic properties of portions of the recording layer comprises means for exposing the mask and the exposed portions of the recording layer to a plasma, wherein the magnetic properties of at least one layer in the exposed portions of the recording layer are changed.

Claim 19 (original): The system of claim 17, further comprising means for etching away a portion of the recording layer in the exposed portions of the recording layer to form grooves in at least one layer within the exposed portions of the recording layer.

Claim 20 (original): The system of claim 19, wherein the means for changing the magnetic properties of portions of the recording layer comprises means for exposing the mask and the exposed portions of the recording layer to a plasma, wherein the magnetic properties of at least one layer in the exposed portions of the recording layer are changed.

Claim 21 (original): The system of claim 16, where in the means for defining a pattern in the mask compresses portions of the mask.

Claim 22 (original): The system of claim 21, further comprising means for removing the compressed portions of the mask in order to expose portions of the recording layer.

Claim 23 (withdrawn): The system of claim 22, wherein the means for changing the magnetic properties of portions of the recording layer comprises means for exposing the mask and the exposed portions of the recording layer to a plasma, wherein the magnetic properties of at least one layer in the exposed portions of the recording layer are changed.

Claim 24 (original): The system of claim 22, further comprising means for etching away a portion of the recording layer in the exposed portions of the recording layer to form grooves in at least one layer within the exposed portions of the recording layer.

Claim 25 (original): The system of claim 24, wherein the means for changing the magnetic properties of portions of the recording layer comprises means for exposing the mask and the exposed portions of the recording layer to a plasma, wherein the magnetic properties of at least one layer in the exposed portions of the recording layer are changed.

Claim 26 (canceled).

Claim 27 (canceled).